Photomask Japan 2018 Poster Presentation

as of January 26

Date	Session Time	Session No.	Session Title	Program No.	Presentation Title	Name	Affiliation
April 19	15:20 - 17:00	9A	**Mask technologies**	9A-1	CD-SEM Optimization to Minimize Electron Beam Impact on Photoresist for Accurate Calibration of Final CD	Sebastian Lipfert	Adavanced Mask Technology Center (AMTC)
				9A-2	Advanced ceramic protective lifetime prolong for particle control	Yuan Hsu	Photronics DNP Mask Corp.
				9A-3	Intra-field mask-to-mask overlay, separating the mask writing from the dynamic pellicle contribution	Richard van Haren	ASML
				9A-4	Achieve High Hotspot Detection Accuracy by Pattern Scoring	Xiang Fang	Mentor Graphics Corporation
				9A-5	The development of extreme ultraviolet lithography mask in China	Hailiang Li	Laboratory of Microelectronic Devices&Integrated Technology, Institute of Microelectronics Chinese Academy of Science
				9A-6	Enabling Accurate and Cost-Effective Registration Metrology on EUVL Masks	Runyuan Han	KLA-Tencor MIE GmbH
				9A-7	EUV Mask with Advanced Hybrid Black Border Suppressing EUV and DUV OoB Light Reflection	Genta Watanabe	Toppan Printing Co., Ltd
		9B	**Mask/lithography related technologies in academia**	9B-1	SingleFocusSpiralZonePlates	Yonghao Liang	Key Laboratory of Microelectronic Devices & Integrated Technology, Institute of Microelectronics, Chinese Academy of Sciences
				9B-2	Exposure characteristics of ternary copolymerization positive tone electron beam resist containing p-chloro-a-methylstyrene	Kenta Tamaru	Yamaguchi University
				9B-3	Dependence of Dissolution Kinetics of Main-Chain Scission Type Resists on Molecular Weight	Akihiro Konda	Osaka University
				9B-4	Simulation of fogging electron trajectories in a scanning electron microscope	Yuka Ito	Osaka Institute of Technology
				9B-5	Measurement of the flare electron current in scanning electron microscope	Kentaro Morimoto	Osaka Institute of Technology
				9B-6	Contribution of flare electrons to produce potential distribution on an insulator film by electron beam irradiation	Hideya Mizuno	Osaka Institute of Technology